



Form PTO 1449 U.S. DEPARTMENT OF  
(Modified) COMMERCE  
PATENT AND TRADEMARK  
OFFICE

ATTY. DOCKET NO.

8733.215.00

08/671,376

APPLICANT

10/052767

Tieer GU et al.

FILING DATE

1/23/02

GROUP

2822-2813

LIST OF REFERENCES CITED BY APPLICANT  
(Use Several Sheets if Necessary)

Date: February 5, 2001

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	AA	6,100,954	08/08/00	Kim et al.	349	138	—
<i>QMD</i>	AB	4,636,038	01/1987	Kitahara et al.	350	339	—
<i>QMD</i>	AC	4,943,838	07/1990	Ukai	257	410	—
<i>QMD</i>	AD	5,072,262	12/1991	Uekita et al.	257	410	—
<i>QMD</i>	AE	5,229,644	07/1993	Wakai et al.	257	749	—
<i>QMD</i>	AF	5,246,782	09/1993	Kennedy et al.	428	421	—
<i>QMD</i>	AG	5,294,820	03/1994	Gemma et al.	257	324	—
<i>QMD</i>	AH	5,486,493	01/1996	Jeng	437	195	—

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO
<i>QMD</i>	AI	63-279228	11/1988	JAPAN	
<i>QMD</i>	AJ	63-289965	11/1988	JAPAN	
<i>QMD</i>	AK	04-068318	03/1992	JAPAN	
<i>QMD</i>	AL	04-163528	06/1992	JAPAN	
<i>QMD</i>	AM	05-203936	08/1993	JAPAN	

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>QMD</i>	AN	M.J. Radler et al., <i>Cyclotene™ Advanced Electronics Resins for High-Aperture AMLCD Applications</i> , SID 96 APPLICATIONS DIGEST, pp. 33-36 (1996).
<i>QMD</i>	AO	Eric P. Finchem et al., <i>A Multi-Level High Density Interconnect Process Designed &amp; Developed for Manufacturability</i> , TriQuint Semiconductor, Inc., Beaverton, OR, USA
<i>QMD</i>	AP	M.J. Radler et al., <i>Benzocyclobutene Dielectric Resins for Flat Panel Display Applications</i> , Proceedings of the 3 <sup>rd</sup> Annual Display Manufacturing Technology Conference, pp: 123-4, 1996 (Conference date: February 6-8, 1996)

EXAMINER

*Jennifer M. M...*

DATE CONSIDERED

2/28/03

\*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

\*\*English-language abstract provided.

Form PTO 1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 8733.215.00 08/671,376 APPLICANT <u>10/052767</u> Tieer GU et al. FILING DATE <u>1/23/02</u> <del>June 27, 1996</del> GROUP <u>2822-2813</u>				
LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary) Date: <u>January 29, 2001</u>						
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<u>QMD</u>	BA	5,585,951	12/1996	Noda et al.	349	122
<u>QMD</u>	BB	5,591,676	01/1997	Hughes et al.	438	702
<u>QMD</u>	BC	5,641,974	06/1997	Den Boer et al.	257	59
<u>QMD</u>	BD	5,675,187	10/1997	Numata et al.	257	758
<u>QMD</u>	BE	5,721,596	02/1998	Kochi	349	2
<u>QMD</u>	BF	5,721,601	02/1998	Yamaji et al.	349	138
<u>QMD</u>	BG	5,821,621	10/1998	Jeng	257	759
<u>QMD</u>	BH	6,038,008	03/14/2000	Kim et al.	349	138
FOREIGN PATENT DOCUMENTS						
	DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
<u>QMD</u>	BI	0-536-898 A1	04/1993	EUROPEAN PATENT OFFICE (In English)		
<u>QMD</u>	BJ	0-589-478 A2	03/1994	EUROPEAN PATENT OFFICE (In English)		
<u>QMD</u>	BK	0-589-478 A3	03/1994	EUROPEAN PATENT OFFICE (In English)		
<u>QMD</u>	BL	0-486-047 A2	05/1992	EUROPEAN PATENT OFFICE (In English)		
<u>QMD</u>	BM	0-486-047 A3	05/1992	EUROPEAN PATENT OFFICE (In English)		
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)						
<u>QMD</u>	BN	Stanley Wolf et al., <i>Silicon Processing For The VLSI Era</i> , Vol. 1, Process Technology, Lattice Press, Sunset Beach, CA., 1986				
<u>QMD</u>	BO	Tadanori Shimoto et al. <i>High Density Multilayer Substrate Using Benzocyclobutene Dielectric</i> , IMC 1992 Proceedings, Yokohama, June 3-5, 1992, pp: 325-30				
<u>QMD</u>	BP	Willem den BOER et al., <i>High Aperture TFT LCD using Polymer Interlevel Dielectric</i> , OIS Optical Imaging Systems, Inc., Northville, MI, USA				
EXAMINER: <u>Janifer M. Olo</u>				DATE CONSIDERED <u>2/18/03</u>		
*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						
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<p>Form PTO 1449 U.S. DEPARTMENT OF COMMERCE (Modified) PATENT AND TRADEMARK OFFICE</p> <p>LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary)</p> <p>Date: <u>January 29, 2001</u></p>	<p>ATTY. DOCKET 8733.215.00</p>	<p>08/671,376- <u>10/052767</u></p>
<p>APPLICANT Tieer GU et al.</p>		
<p>FILING DATE June 27, 1996 <u>1/23/02</u></p>		<p>GROUP <del>2822</del> 2813</p>

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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	CA	4,431,272	02/1984	Yazawa et al.	350	336	—
<i>QMD</i>	CB	4,451,525	05/1984	Kawazoe et al.	428	213	—
<i>QMD</i>	CC	5,408,345	04/1995	Mitsui et al.	349	42	—
<i>QMD</i>	CD	5,411,629	05/1995	Warfield	216	34	—
<i>QMD</i>	CE	5,500,750	03/1996	Kanbe et al.	349	42	—
<i>QMD</i>	CF	5,600,458	02/1997	Okano et al.	349	44	—
<i>QMD</i>	CG	5,724,111	03/1998	Mizobata et al.	349	113	—
<i>QMD</i>	CH	5,844,647	12/1998	Maruno et al.	349	138	—

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		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO	
<i>QMD</i>	CI	0-616-241 A2	09/1994	EUROPEAN PATENT OFFICE (In English)		
<i>QMD</i>	CJ	0-714-140 A1	05/1996	EUROPEAN PATENT OFFICE (In English)		
<i>QMD</i>	CK	2-311-653	10/1997	UNITED KINGDOM (In English)		
<i>QMD</i>	CL	41-40-180 A1	12/1992	DENMARK		
<i>QMD</i>	CM	4-257826A	09/1992	JAPAN (English Abstract only)		

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>QMD</i>	CN	M.W. Friends, <i>Determination of Dielectric Constant for Fuji Clear</i> , 3/7/1996, pp:1-2, including Table
<i>QMD</i>	CO	Willem den BOER, <i>A Two-Diode Pixel Circuit and Addressing Method for MIM LCDs</i> , OIS Optical Systems, Inc., Northville, MI, USA
<i>QMD</i>	CP	Tech Notes, Advanced Electronics Resins, <i>Processing Guide for Photo-Imageable BCB</i> , Dow Chemical Co., pp: 1-4

EXAMINER <i>James M. Ma</i>	DATE CONSIDERED <u>2/28/03</u>
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APPLICANT

Tieer GU et al.

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June 27, 1996

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JMD	DA	5,177,588	01/05/1993	li et al.	257	640	—
JMD	DB	5,045,905	09/03/1991	Motai et al.	357	207	—
JMD	DC	5,281,546	01/25/1994	Possin et al.	437	40	—
JMD	DD	5,003,356	03/26/1991	Wakai et al.	357	4	—
JMD	DE	5,847,720	12/08/1998	Dunand	347	1	—
JMD	DF	5,578,630	11/19/1996	Fujita	324	760	—
JMD	DD	5,920,084	07/06/1999	Gu et al.	257	59	—
JMD	DH	5,780,874	07/14/1998	Kudo	257	77	—

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JMD	DI	10-133165	05/1998	JAPAN		
	DJ					
	DK					
	DL					
	DM					

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JMD	DN	Michael Schier, <i>Reactive Ion Etching of Benzocyclobutene Using a Silicon Nitride Dielectric Etch Mask</i> , J. Electrochem. Soc., Vol. 142, No. 9, September 1995, pp: 3238-40
JMD	DO	Donald Peretrie, et al., <i>Benzocyclobutene as a Planarization Resin for Flat Panel Displays</i> , SPIE Vo., 1965, Liquid Crystal Materials, Device, and Applications (1992), pp: 331-7
	DP	

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*Jennifer M. Odo*

DATE CONSIDERED

2/28/02

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Form PTO 1449

(Modified)

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8733.215.00

08/671,376

Copies of Forms PTO-1449 and PTO-892 from  
parent applications Serial Nos. 08/671,376 and  
08/470,271  
Page 5 of 12

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LIST OF REFERENCES CITED BY APPLICANT  
(Use Several Sheets if Necessary)Date: January 29, 2001

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Tieer GU et al.

FILING DATE

June 27, 1998

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GROUP

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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	EA	5,477,359	12/19/1995	Okazaki	359	77	—
<i>QMD</i>	EB	5,287,208	02/15/1994	Shimoto et al.	359	75	—
<i>QMD</i>	EC	5,994,721	11/30/1999	Zhong et al.	257	89	—
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		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
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## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

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EXAMINER

*James M. DeLo*

DATE CONSIDERED

4/28/03

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Notice of References Cited			Application No. 08/671,376		Gu et al	
			Examiner Michael Trinh		Group Art Unit 2822	
					Page 1 of 1	
U.S. PATENT DOCUMENTS						
	DOCUMENT NO.	DATE	NAME		CLASS	SUBCLASS
A	5,477,359	12/19/95	Okazaki		359	77
B	5,559,055	9/24/98	Chang et al		438	586
C	5,780,874	7/14/98	Kudo		257	642
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*Quayle SM Dole*

2/20/03

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Application No.  
**08/671,376**

Gu et al

Examiner  
**Michael Trinh**

Group Art Unit  
**2813**

Page 1 of 1

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<i>2/28/03</i>	5,466,535	11/14/95	Higgins et al	428	483
<i>2/28/03</i>	5,477,360	12/19/95	Sunohara et al	349	132
<i>2/28/03</i>	5,585,951	12/17/98	Noda et al	349	122
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**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

	DOCUMENT (including Author, Title, Source, and Pertinent Pages)	DATE
<i>2/28/03</i>	Wolf et al, "Silicon Processing for the VLSI Era", vol 1, pp 407-408,418-421,428-429	1988
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*Gu et al 2/28/03*

PTO/SB/08 (11-90)



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## Section 2. Form PTO - 1449 (Modified)

<b>FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE</b> <b>(Modified) PATENT AND TRADEMARK OFFICE</b>  <b>INFORMATION DISCLOSURE</b> <b>STATEMENT BY APPLICANT</b>  (Use several sheets if necessary)  (37 CFR 1.98(b))	<b>ATTY. DOCKET NO.</b> 12190.293	<b>SERIAL NO.</b> 08/671,376
	<b>APPLICANT</b> den BOER, ET. AL. 10/052767	
	<b>FILE DATE</b> 6/27/96	<b>GROUP</b> 2813

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 10/052767  
 01/23/02

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication\*)

EXAMINER	DATE CONSIDERED
<i>[Signature]</i>	2/29/03

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GROUP	2813
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(Information Disclosure Statement - Section 2, FORM PTO - 1449 (Modified))

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)		Applicant: <b>Don Bosa, Sr. et. al.</b> Filing Date: <b>6/27/96</b> Class: <b>2832</b>	
Application Number: <b>12150.293</b> Application Date: <b>08/671-376</b>		Filing Date: <b>10/05/2007</b> Class: <b>2832</b>	

U.S. PATENT DOCUMENTS		EXAMINER INITIAL	
NAME DATE	DOCUMENT NUMBER DATE	CLASS SUBCLASS	IF APPROPRIATE
G. et. al.	59200847/499	—	—

FOREIGN PATENT DOCUMENTS			
DOCUMENT NUMBER DATE	COUNTRY CLASS SUBCLASS	YES NO	Translation
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EXAMINER DATE CONSIDERED	2/28/03
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